LETTERS

Effect of surface derived hydrocarbon impurities on Ar plasma properties
Nick Fox-Lyon, Gottlieb S. Oehrlein and Valery Godyak
J. Vac. Sci. Technol. A **32**, 030601 (2014); http://dx.doi.org/10.1116/1.4867158

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Influence of pulse power amplitude on plasma properties and film deposition in high power pulsed plasma enhanced chemical vapor deposition
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Effect of WN content on toughness enhancement in $V_{1-x}W_xN$/MgO(001) thin films
H. Kindlund, D. G. Sangiovanni, J. Lu, J. Jensen, V. Chirita, I. Petrov, J. E. Greene and L. Hultman
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Characterizing low-frequency oscillation of Hall thrusters by dielectric wall temperature variation
Guo Ning, Wei Liqiu and Ding Yongjie
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Dandan Wang, Pik Kee Tan, Maggie Yamin Huang, Jeffrey Lam and Zhihong Mai
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Atmospheric-pressure low-temperature plasma processes for thin film deposition
Hiroaki Kakiuchi, Hiromasa Ohmi and Kiyoshi Yasutake
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INTERFACES

Control of the interfacial abruptness of Au-catalyzed Si-$Si_{1-x}Ge_x$ heterostructured nanowires grown by vapor–liquid–solid
Priyanka Periwal, Thierry Baron, Laurence Latu-Romain, Bassem Salem, Franck Bassani,Gilles Patriarche and Pascal Gentile

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PLASMA SCIENCE AND TECHNOLOGY

Comparative study of GaN mesa etch characteristics in Cl_2 based inductively coupled plasma with Ar and BCl_3 as additive gases

Dipendra Singh Rawal, Henika Arora, Bhupender Kumar Sehgal and Rangarajan Muralidharan

J. Vac. Sci. Technol. A **32**, 031301 (2014); http://dx.doi.org/10.1116/1.4868616

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Precision plasma etching of Si, Ge, and Ge:P by SF_6 with added O_2

Chalermwat Wongwanitwattana, Vishal A. Shah, Maksym Myronov, Evan H. C. Parker, Terry Whall and David R. Leadley

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Argon–oxygen dc magnetron discharge plasma probed with ion acoustic waves

Partha Saikia, Bipul Kumar Saikia, Kalyan Sindhu Goswami and Arindam Phukan

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Observation of radio frequency ring-shaped hollow cathode discharge plasma with MgO and Al electrodes for plasma processing

Yasunori Ohtsu and Naoki Matsumoto

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Portable total reflection x-ray fluorescence analysis in the identification of unknown laboratory hazards

Ying Liu, Susumu Imashuku, Nobuharu Sasaki, Long Ze, Jun Kawai, Shotaro Takano,Yoshiki Sohrin, Hiroko Seki and Hiroya Miyauchi

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Microstructure of surface cerium hydride growth sites

Martin Brierley, John Knowles, Neil Montgomery and Michael Preuss

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Recycling gold nanohole arrays

Donna Hohertz, Sean F. Romanuik, Bonnie L. Gray and Karen L. Kavanagh
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Xiaokang Huang, Gaurav Gupta, Weixiang Gao, Van Tran, Bang Nguyen, Eric McCormick,Yongjie Cui, Yinbao Yang, Craig Hall and Harold Isom
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Effect of stacking sequence on crystallization in Al/a-Ge bilayer thin films
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Electrical conductance behavior of thin Ni catalyst films during intermittent direct current magnetron sputtering
Yuji Kusumoto, Hiroshi Furuta, Kazuki Sekiya, Hirofumi Koji and Akimitsu Hatta
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Phase formation and morphological stability of ultrathin Ni-Co-Pt silicide films formed on Si(100)
Peng Xu, Tomas Kubart, Xindong Gao, Dongping Wu and Shi-Li Zhang
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Analytic expressions for atomic layer deposition: Coverage, throughput, and materials utilization in cross-flow, particle coating, and spatial atomic layer deposition
Angel Yanguas-Gil and Jeffrey W. Elam
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Effect of NH_3/N_2 ratio in plasma treatment on porous low dielectric constant SiCOH materials
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Low sheet resistance titanium nitride films by low-temperature plasma-enhanced atomic layer deposition using design of experiments methodology
Micheal Burke, Alan Blake, Ian M. Povey, Michael Schmidt, Nikolay Petkov, Patrick Carolan and Aidan J. Quinn
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ZrN coatings deposited by high power impulse magnetron sputtering and cathodic arc techniques
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Optical characteristics of nanocrystalline $Al_xGa_{1-x}N$ thin films deposited by hollow cathode plasma-assisted atomic layer deposition
Eda Goldenberg, Cagla Ozgit-Akgun, Necmi Biyikli and Ali Kemal Okyay
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Growth and electrical properties of *in situ* phosphorus-doped polycrystalline silicon films using Si_3H_8 and PH_3
Byongju Kim, Hyunchul Jang, Sun-Wook Kim, Dae-Seop Byeon, Sangmo Koo, Jason S. Song and Dae-Hong Ko
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Plasma-enhanced atomic layer deposition of silicon dioxide films using plasma-activated triisopropylsilane as a precursor
Ki-Moon Jeon, Jae-Su Shin, Ju-Young Yun, Sang Jun Lee and Sang-Woo Kang
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Time-resolved surface infrared spectroscopy during atomic layer deposition of

TiO_2 using tetrakis(dimethylamido)titanium and water
Brent A. Sperling, John Hoang, William A. Kimes, James E. Maslar, Kristen L. Steffens and Nhan V. Nguyen
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Low-temperature growth of gallium nitride films by inductively coupled-plasma-enhanced reactive magnetron sputtering
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VACUUM SCIENCE AND TECHNOLOGY

Microtrenching-free two-step reactive ion etching of 4H-SiC using $NF_3/HBr/O_2$ and Cl_2/O_2
Yuan-Hung Tseng and Bing-Yue Tsui
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Use of non evaporable getter pumps to ensure long term performances of high quantum efficiency photocathodes
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Influencing factors on the sensitivity of MEMS-based thermal conductivity vacuum gauges
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Hydrogen traps in the outgassing model of a stainless steel vacuum chamber
Robert F. Berg
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Calibration of tip and sample temperature of a scanning tunneling microscope using a

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Matthias Stocker, Holger Pfeifer and Berndt Koslowski

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BRIEF REPORTS AND COMMENTS

Vacuum compatibility of 3D-printed materials

Alexander P. Povilus, Caroline J. Wurden, Zak Vendeiro, Marcelo Baquero-Ruiz and Joel Fajans

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